

<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>  (PTO-1449)			ATTY. DOCKET NO. <b>60188-634</b>	SERIAL NO.			
			<b>APPLICANT</b> <b>Endo MASAYUKI, et al.</b>				
			<b>FILING DATE</b> <b>August 20, 2003</b>	<b>GROUP</b>			
<b>U.S. PATENT DOCUMENTS</b>							
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<b>FOREIGN PATENT DOCUMENTS</b>							
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						Yes	No
<i>mr</i>		JP-2001-316863 (w/ English Abstract)	11/16/2001	TDK CORP.			
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
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<i>mr</i>		M. Svitkes et al., "Immersion lithography at 157 nm", J. Vac. Sci. Technol., B19(6), (2001), pp. 2353-2356.					
<b>EXAMINER</b> <i>Knor Hoang</i>				<b>DATE CONSIDERED</b> <i>3/20/05</i>			

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